

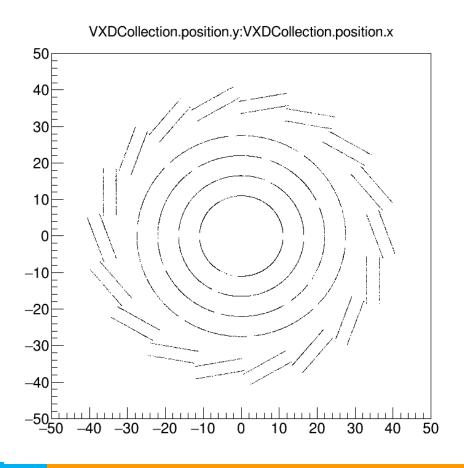
# **CEPC** vertex Detector

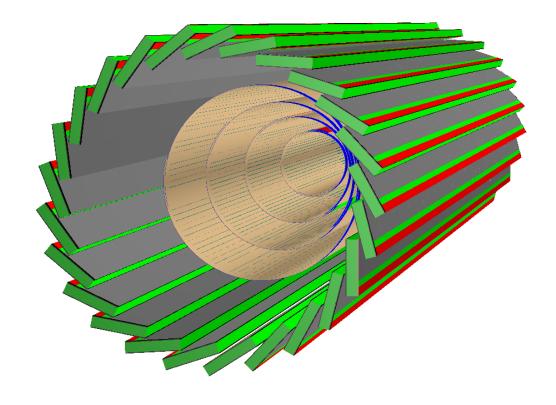
Zhijun Liang



#### **Software for Stitching Vertex Detector**

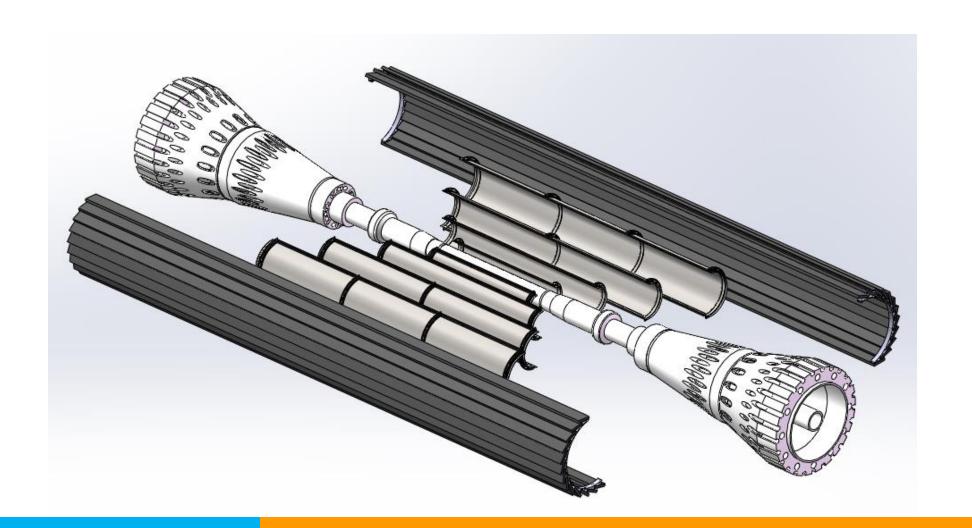
- News update
  - Reconstruction on stitching + ladder layout is now ready
  - To do: Performance study & layout optimization





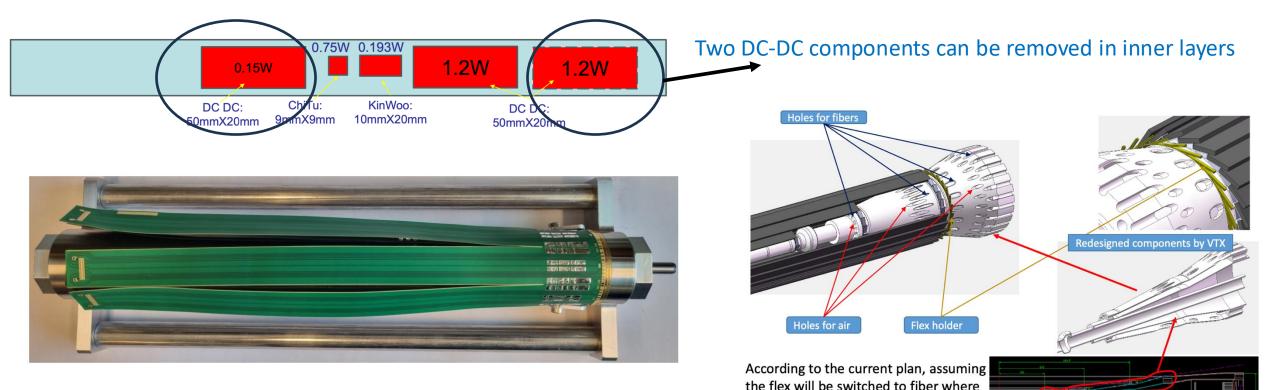
# Mechanics update

Support structure update and installation scheme



### Vertex technologies: Cable and service

- Revisit the space in MDI region for cable and service
  - Working to optimize the dimension on flexible PCB and components

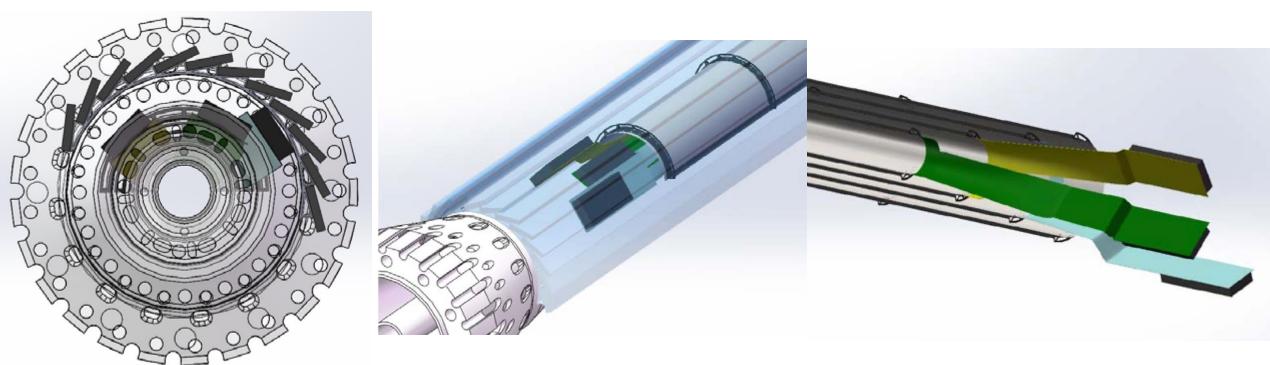


beyond and near the end of the ladder.

# Space for service and cabling

By Jinyu

- Two Flexible PCB + DC-DC components for one layer (upper and lower part)
- still optimizing space to fit in all cabling



## Summary

- Software for Stitching Vertex Detector is now ready
- In progress of optimizing PCB, service and cable space for inner layer

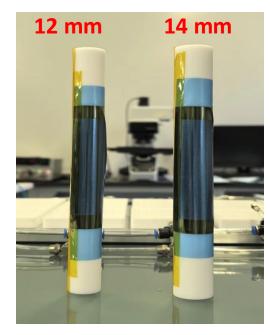
#### International collaboration

- Contacting with Jérôme Baudot, vertex group leader in IPHC/CNRS
- Jérôme Baudot is planning to join CEPC workshop 2024 in person
- Wei Wei, Ying, Yunpeng and I will join PIXEL2024 in IPHC in person
  - A few talks about the CEPC vertex accepted in PIXEL2024 (Nov 18-22)

## Stitching R & D

- New thinned dummy wafers received.
  - Thinned to ~30um
  - Expected to bent it to ~11mm radius

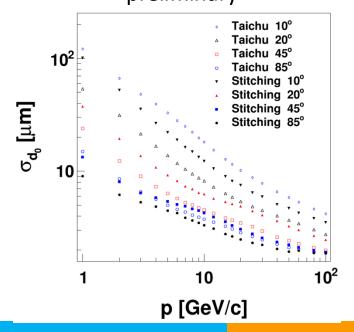
By Mingyi

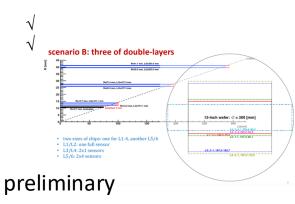


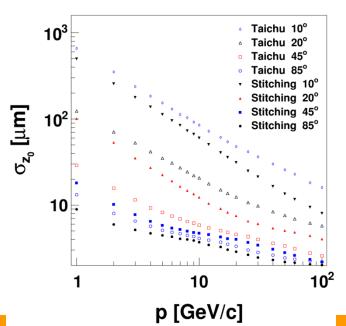
	Status	CEPC Final goal
Bent silicon with radius	Bent Dummy wafer radius ~12mm	Bent final wafer with radius ~11mm

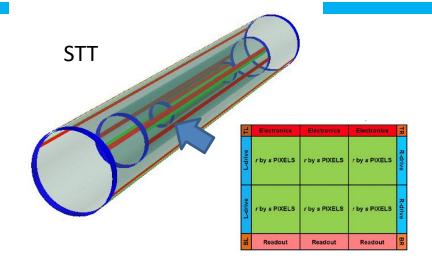
#### Status of Software for Stitching Vertex Detector

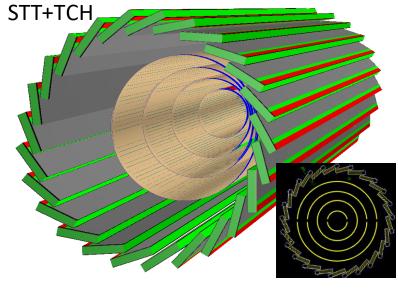
- Geometry
  - TaiCHu → STiTching → composite (TCH+STT)
- Reconstruction
  - Planar measurement → Cylinder measurement
  - Processor for STT
- Validation
  - STT VS TCH on three of double-layers
- Todo
  - Reconstruction on STT+TCH
  - Performance & layout preliminary







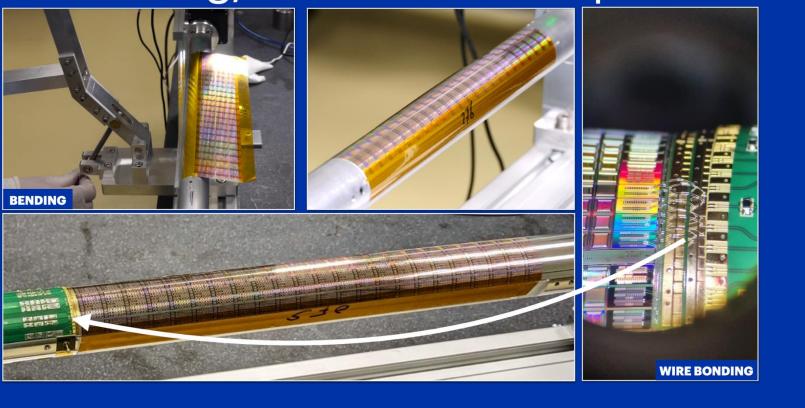


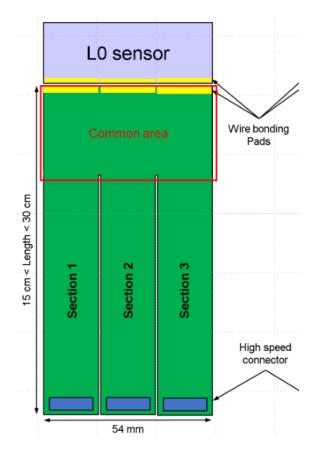


### Vertex technologies: Cable and service

Refine the design for wire bonding and PCB

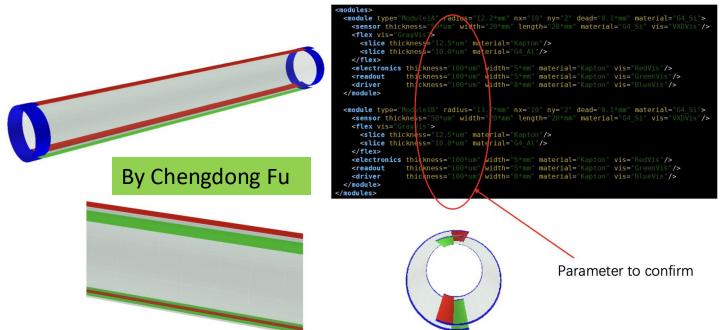
ITS3 bending/interconnection procedure

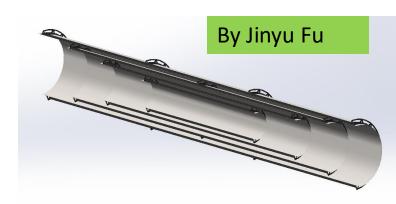


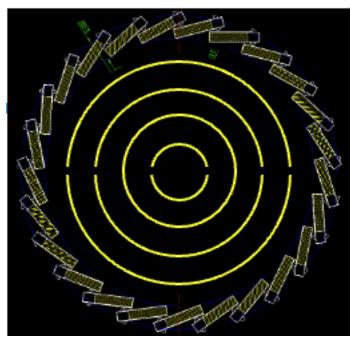


## **Update in CEPCSW**

- Stitching layer layout is implemented in CEPCSW
  - Dead area is also considered
  - Digitization is OK now, can be used for BG simulation
  - Code for reconstruction is still under development
  - Module->Layer







by Wei Wei

## **Total power**

#### **VTX-Power Link**



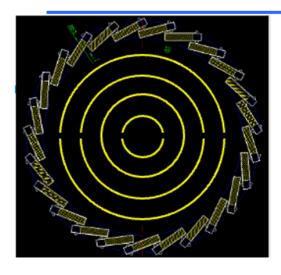
Layer	Comme nt	Power/chi p	Chips/Ro w	Power /row	Rows	Chip Power of Layers	Power consumed of BaSha (15%)	Total Power/Layer
1	Stitching	200mW	8	1.6W	2*2=4	6.4W	0.96W	8.51W
2	Stitching	200mW	12	2.4W	3*2=6	14.4W	2.16W	17.71W
3	Stitching	200mW	16	3.2W	4*2=8	25.6W	3.84W	30.59W
4	Stitching	200mW	20	4W	5*2=10	40W	6W	47.15W
5	Ladder- side0	200mW	29	5.8W	25	145W	21.75W	167.9W
6	Ladder- side1	200mW	29	5.8W	25	145W	21.75W	167.9W

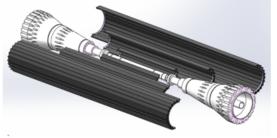
- 探测器前提假设一致,每芯片功耗估算为200mW(40mW/cm2 \* 2.6cm\*1.6cm)
- @40MHz (BX=25ns), 如按15ns, 功耗将成倍增加
- 主要功耗贡献:模拟静态功耗+数据接口,不随本底数据率变化,因此不考虑按各层本底的功耗 scaling down
- 设BaSha DC-DC效率为85%,则功耗开销为15%
- 每行固定功耗:数据接口1W+数据接口开销0.15W=1.15W
- · 总功耗439.8W(可按1~3层、4层各一个电源通道, 5、6每层各两个电源通道@100W/ch考虑, 共6个电源通道)

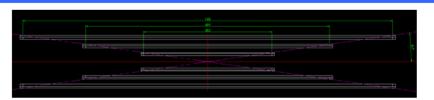
#### **Total Data rate**

#### VTX

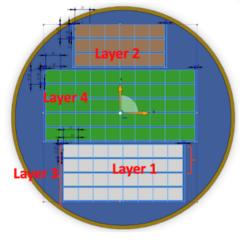








• 安全因子1.5,加速器50MW,按内层2Gbps/chip为数据率基准,按higgs mode本底比例计算各层,各层芯片数量内四层以RSU为单位,外两层(double sided)以芯片为单位



Lay er	Comment	Data Rate/chip	Chips/ Row	Data rate/row	Rows	Links@10Gbps
1	Stitching	2Gbps	8	16G	2*2=4	2*4=8
2	Stitching	1.3Gbps	12	15.6G	3*2=6	2*6=12
3	Stitching	0.27Gbps	16	4.3G	4*2=8	1*8=8
4	Stitching	0.25Gbps	20	5G	5*2=10	1*10=10
5	Ladder- side0	0.16Gbps	29	4.64G	25	1*25=25
6	Ladder- side1	0.16Gbps	29	4.64G	25	1*25=25